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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
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10/563,701

04/03/2006

Andreas Seifert

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2956

24628 7590 06/27/2008

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EXAMINER

SHAFFER, RICKY D

ART UNIT

PAPER NUMBER

2872

MAIL DATE

DELIVERY MODE

06/27/2008

PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Office Action Summary	Application No. 10/563,701	Applicant(s) SEIFERT ET AL.	
	Examiner Ricky D. Shafer	Art Unit 2872	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 1 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 05 January 2006.
- 2a) ☐ This action is **FINAL**. 2b) ☐ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 29-66 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☐ Claim(s) _____ is/are rejected.
- 7) ☐ Claim(s) _____ is/are objected to.
- 8) ☒ Claim(s) 29-66 are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on _____ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some * c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
 2. ☐ Certified copies of the priority documents have been received in Application No. _____.
 3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- | | |
|--|---|
| 1) <input type="checkbox"/> Notice of References Cited (PTO-892) | 4) <input type="checkbox"/> Interview Summary (PTO-413) |
| 2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948) | Paper No(s)/Mail Date. _____ |
| 3) <input type="checkbox"/> Information Disclosure Statement(s) (PTO/SB/08) | 5) <input type="checkbox"/> Notice of Informal Patent Application |
| Paper No(s)/Mail Date _____ | 6) <input type="checkbox"/> Other: _____ |

Art Unit: 2872

1. Restriction is required under 35 U.S.C. 121 and 372.

This application contains the following inventions or groups of inventions which are not so linked as to form a single general inventive concept under PCT Rule 13.1.

In accordance with 37 CFR 1.499, applicant is required, in reply to this action, to elect a single invention to which the claims must be restricted.

Group I, claim(s) 32 and 35, drawn to a method for producing mirror facets for a facet mirror by recessing or machining a reflecting optical surface into or on the mirror facet, wherein an edge of the mirror facet having a sharpness of less than 50 micrometers.

Group II, claim(s) 34 and 36, drawn to a method for producing mirror facets for a facet mirror by recessing or machining a reflecting optical surface into or on the mirror facet, wherein the optical surface has a particular tilting angle accuracy of less than 3 inches.

Group III, claim(s) 37, drawn to a method for producing mirror facets for a facet mirror in illuminating devices for projection exposure machines in microlithography by using radiation in the extreme ultraviolet region, wherein tilting angles are recessed or machined into or on an optical surface of the mirror facet and provide with a reflecting layer and then arrange on a mirror support body.

Group IV, claim(s) 38, drawn to a method for producing mirror facets for a facet mirror in illuminating devices for projection exposure machines in microlithography by using radiation in the extreme ultraviolet region, wherein tilting angles are recessed or machined into or on an optical surface of the mirror facet and the optical surface has a high aspect ratio.

Group V, claim(s) 40, drawn to a method for producing mirror facets for a facet mirror in illuminating devices for projection exposure machines in microlithography by using radiation in the extreme ultraviolet region, wherein a plurality of tilting angles are recessed or machined into or on an optical surface of the mirror facet.

Group VI, claim(s) 41 and 43, drawn to a method for producing mirror facets for a facet mirror in illuminating devices for projection exposure machines in microlithography by using radiation in the extreme ultraviolet region, wherein tilting angles are recessed or machined into or on an optical surface of the mirror facet and the mirror facet is brought between two bearing bodies.

Group VII, claim(s) 42, drawn to a method for producing mirror facets for a facet mirror in illuminating devices for projection exposure machines in microlithography by using radiation in the extreme ultraviolet region, wherein tilting angles are recessed or machined into or on an optical surface of the mirror facet and the tilting angle of the mirror facet is set by a screw device.

Art Unit: 2872

Group VIII, claim(s) 44-54, drawn to a method for producing mirror facets for a facet mirror in illuminating devices for projection exposure machines in microlithography by using radiation in the extreme ultraviolet region, wherein tilting angles are recessed or machined into or on an optical surface of the mirror facet and the mirror facet is arranged on a support body in a machine tool.

Group IX, claim(s) 55-60, 65 and 66, drawn to a method for producing mirror facets for a facet mirror in illuminating devices for projection exposure machines in microlithography by using radiation in the extreme ultraviolet region, wherein tilting angles are recessed or machined into or on an optical surface of the mirror facet wherein a plurality of mirror facets are produced.

Group X, claim(s) 61 and 62, drawn to a positioning apparatus for a mirror facet on a support body, wherein tilt angles are recessed into an optical surface of the mirror facet having a U-shaped body, end measures for fixing a mirror facet position and clamping elements for pressing the mirror facet against the end measure.

Group XI, claim(s) 63 and 64, drawn to a positioning apparatus for a mirror facet on a support body, wherein tilt angles are recessed into an optical surface of the mirror facet having auxiliary elements for enlarging the machine area of the mirror facet.

Claims 29, 30 and 39 will be examined along with any one of the elected Groups III-IX.

Claim 31 and 33 will be examined along with any one of the elected Groups I-XI.

2. The inventions listed as Groups I-XI do not relate to a single general inventive concept under PCT Rule 13.1 because, under PCT Rule 13.2, they lack the same or corresponding special technical features for the following reasons: It appears any special technical feature of the above mentioned inventions relate to the separate features of the particular invention, absent an allowable linking claim to the above mentioned inventions.

3. Applicant is advised that the reply to this requirement to be complete must include (i) an election of a species or invention to be examined even though the requirement may be traversed (37 CFR 1.143) and (ii) identification of the claims encompassing the elected invention.

The election of an invention or species may be made with or without traverse. To preserve a right to petition, the election must be made with traverse. If the reply does not

Art Unit: 2872

distinctly and specifically point out supposed errors in the restriction requirement, the election shall be treated as an election without traverse.

4. Applicant is reminded that upon the cancellation of claims to a non-elected invention, the inventorship must be amended in compliance with 37 CFR 1.48(b) if one or more of the currently named inventors is no longer an inventor of at least one claim remaining in the application. Any amendment of inventorship must be accompanied by a request under 37 CFR 1.48(b) and by the fee required under 37 CFR 1.17(i).


5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ricky D. Shafer whose telephone number is (571) 272-2320.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

RDS

June 19, 2008

/Ricky D. Shafer/
Primary Examiner
Art Unit 2872

<i>Application Number</i> 	Application/Control No.	Applicant(s)/Patent under Reexamination	
	10/563,701	SEIFERT ET AL.	
	Examiner	Art Unit	
	Ricky D. Shafer	2872	